

(FILE 'HOME' ENTERED AT 15:19:41 ON 21 JUL 2006)

FILE 'CAPLUS' ENTERED AT 15:20:12 ON 21 JUL 2006

L1 STRUCTURE UPLOADED
 S L1

FILE 'REGISTRY' ENTERED AT 15:20:32 ON 21 JUL 2006

L2 0 S L1

FILE 'CAPLUS' ENTERED AT 15:20:32 ON 21 JUL 2006

L3 0 S L2
 S L1

FILE 'REGISTRY' ENTERED AT 15:20:40 ON 21 JUL 2006

L4 0 S L1 FULL

FILE 'CAPLUS' ENTERED AT 15:20:40 ON 21 JUL 2006

L5 0 S L4 FULL

L6 STRUCTURE UPLOADED
 S L6

FILE 'REGISTRY' ENTERED AT 15:22:00 ON 21 JUL 2006

L7 50 S L6

FILE 'CAPLUS' ENTERED AT 15:22:01 ON 21 JUL 2006

L8 48 S L7
 S L6

FILE 'REGISTRY' ENTERED AT 15:22:14 ON 21 JUL 2006

L9 6253 S L6 SSS FULL

FILE 'CAPLUS' ENTERED AT 15:22:16 ON 21 JUL 2006

L10 7382 S L9 SSS FULL

L11 554 S L10 AND(AMMONIUM OR PHOSPHONIUM OR SULFONIUM)

L12 179 S L11 AND QUATERNARY

L13 0 S L12 AND IONIC LIQUID

L14 9 S L12 AND IONIC

L15 6 S L14 AND PY<2002

L16 179 S L10 AND QUATERNARY AND(AMMONIUM OR PHOSPHONIUM OR SULFONIUM)

L17 173 S L10 AND (QUATERNARY AMMONIUM OR QUATERNARY PHOSPHONIUM OR QU

L18 141 S L17 AND PY<2002

L19 7 S L18 AND COMPOSITION

=>

L19 ANSWER 1 OF 7 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2001:916417 CAPLUS

DOCUMENT NUMBER: 136:54231

TITLE: Polyester composition and process therefor

INVENTOR(S): Sun, Yanhui

PATENT ASSIGNEE(S): E. I. Du Pont de Nemours & Co., USA

SOURCE: U.S., 8 pp.

CODEN: USXXAM

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6331606	B1	20011218	US 2000-727792	20001201 <--
PRIORITY APPLN. INFO.:			US 2000-727792	20001201

AB A polyester composition and a process for producing the composition are provided.

The composition comprises repeat units derived from 1,3-propanediol; an organic acid, preferably a dicarboxylic acid, its salt, its ester, or combinations of 2 or more thereof; a polyether diol; and a sulfonated comonomer. The polyether diol can be present in the composition in the range of about 10-80 weight %. The process comprises contacting 1,3-propanediol with the organic acid, the polyether diol, and the sulfonated comonomer. The sulfonated comonomer can have the formula of $(R'OC(O))_2A(R)zS(O)2M$ in which each R' can be the same or different and is each independently hydrogen, a C1-C4 alkyl group, or a C1-C4 hydroxyalkyl group; each R is independently a C1-C4 alkyl group; A is an alkylene or arylene group; z is a number of from 0 to 2; and M is hydrogen, alkali metal ion, alkaline earth metal ion, quaternary ammonium, or ammonium ion.

IT 381165-04-4P, Dimethyl terephthalate-poly(tetramethylene glycol)-1,3-propanediol-dimethyl sodium 5-sulfoisophthalate copolymer
RL: CPS (Chemical process); IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); PRP (Properties); PREP (Preparation); PROC (Process)

(manufacture of polyester composition with good strength properties containing

polyetherdiol and sulfonated monomer)

RN 381165-04-4 CAPLUS

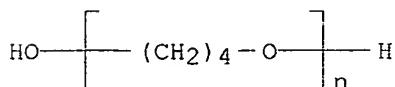
CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with dimethyl 1,4-benzenedicarboxylate, α -hydro- ω -hydroxypoly(oxy-1,4-butanediyl) and 1,3-propanediol (9CI) (CA INDEX NAME)

CM 1

CRN 25190-06-1

CMF (C₄ H₈ O)_n H₂ O

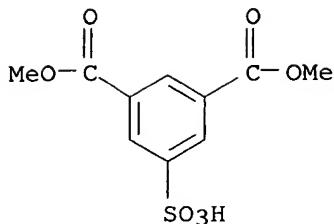
CCI PMS



CM 2

CRN 3965-55-7

CMF C₁₀ H₁₀ O₇ S . Na



● Na

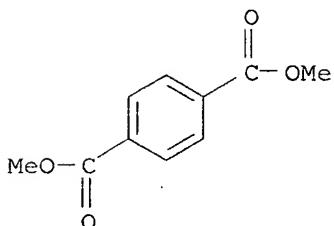
CM 3

CRN 504-63-2
CMF C3 H8 O2

HO—CH₂—CH₂—CH₂—OH

CM 4

CRN 120-61-6
CMF C10 H10 O4



REFERENCE COUNT: 23 THERE ARE 23 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L19 ANSWER 2 OF 7 CAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 2001:261353 CAPLUS
 DOCUMENT NUMBER: 134:303020
 TITLE: Far-UV sensitive positive-working chemically amplified photoresist composition for micro photolithography
 INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiko; Aogo, Toshiaki
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 45 pp.
 CODEM: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.

KIND DATE

APPLICATION NO.

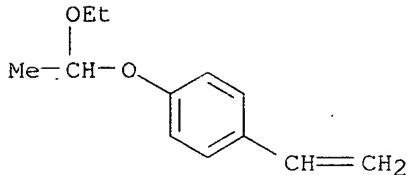
DATE

 JP 2001100421 A2 20010413 JP 1999-280202 19990930 <--
 PRIORITY APPLN. INFO.: JP 1999-280202 19990930
 AB The title composition contains a photoacid generator and a resin increasing the solubility towards an alkali developer by reacting with an acid, wherein the resin has a quaternary ammonium salt group. The addition of the acid-sensitive resin containing quaternary ammonium salt group to the composition provides improved development characteristics and eliminates rough edges on the pattern.
 IT 334642-85-2DP, partially hydrolyzed
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (resin containing quaternary ammonium salt group in far-UV sensitive pos.-working chemical amplified photoresist composition)
 RN 334642-85-2 CAPLUS
 CN Benzenemethanaminium, 4-ethenyl-N,N,N-trimethyl-, salt with 1,3-dimethyl 5-sulfo-1,3-benzenedicarboxylate (1:1), polymer with 1-ethenyl-4-(1-ethoxyethoxy)benzene (9CI) (CA INDEX NAME)

CM 1

CRN 157057-20-0

CMF C12 H16 O2



CM 2

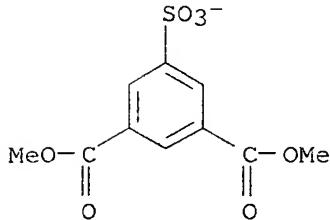
CRN 334642-84-1

CMF C12 H18 N . C10 H9 O7 S

CM 3

CRN 46914-24-3

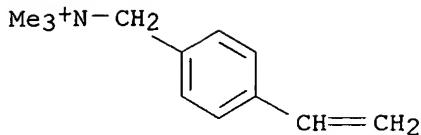
CMF C10 H9 O7 S



CM 4

CRN 46231-82-7

CMF C12 H18 N



L19 ANSWER 3 OF 7 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2000:89395 CAPLUS

DOCUMENT NUMBER: 132:138499

TITLE: Poly(alkylene naphthalate)-based composition
for magnetic recording films

INVENTOR(S): Ura, Ryokatsu; Kosuga, Masahiko; Kurihara, Eisuke

PATENT ASSIGNEE(S): Teijin Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000038499	A2	20000208	JP 1999-136835	19990518 <--
JP 3681574	B2	20050810	JP 1998-138357	A 19980520

PRIORITY APPLN. INFO.:

AB Title composition for recording films with good surface evenness and electrostatic adhesion comprises (A) poly(alkylene naphthalate) prepared from (a) naphthalenedicarboxylic acid-based dicarboxylic acid and (b) aliphatic glycols 100, and (B) inactive microparticles having average diameter 0.01-0.5 μm 0.01-10 parts, wherein the mol ratios of (c) antimony compds. (Sb) and (d) esterifying group-containing quaternary phosphonium sulfonates (S) in the total content of dicarboxylic acids satisfy the relations: $1 \leq \text{Sb} \leq 80$; and $0.001 \leq \text{S/Sb} \leq 0.4$. The composition is prepared by transesterification of (a) and (b) and their polymerization in the presence of (c) and (d). Thus, 100 parts of 2,6-naphthalenedicarboxylate di-Me, 60 parts of ethylene glycol, and 0.7 wt% diethylene glycol were transesterified in the presence of 0.009 part $\text{Ca}(\text{MeCOO})_2 \cdot \text{H}_2\text{O}$ and 0.045 part $\text{Mg}(\text{MeCOO})_2 \cdot 4\text{H}_2\text{O}$, then polymerized with 0.002 part tetrabutylphosphonium 3,5-dicarboxy-1-benzenesulfonate, 0.023 part Sb_2O_3 , and spheric silica (average diameter 0.06 μm), to give 0.05 wt% silica-containing poly(ethylene naphthalate). The composition was dried, melt-extruded, cooled, biaxially stretched 3.6 + 3.9 times, and heat-set to give a 14- μm -thick film with good surface smoothness and electrostatic adhesion.

IT 247027-06-1P, Diethylene glycol-dimethyl 2,6-naphthalene dicarboxylate-ethylene glycol-tetrabutylphosphonium 3,5-dicarboxy-1-benzenesulfonate copolymer 247027-07-2P 247027-08-3P
256957-76-3P

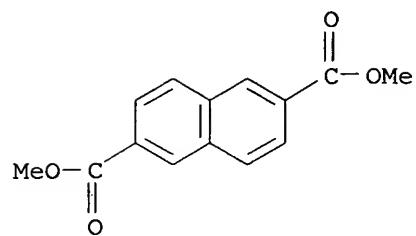
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of poly(alkylene naphthalate)-based composition for magnetic recording films)

RN 247027-06-1 CAPLUS

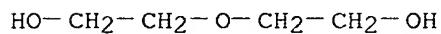
CN Phosphonium, tetrabutyl-, salt with 5-sulfo-1,3-benzeneddicarboxylic acid (1:1), polymer with dimethyl 2,6-naphthalenedicarboxylate, 1,2-ethanediol and 2,2'-oxybis[ethanol] (9CI) (CA INDEX NAME)

CRN 840-65-3
CMF C14 H12 O4



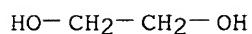
CM 2

CRN 111-46-6
CMF C4 H10 O3



CM 3

CRN 107-21-1
CMF C2 H6 O2

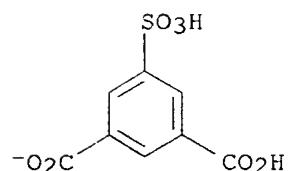


CM 4

CRN 65120-26-5
CMF C16 H36 P . C8 H5 O7 S

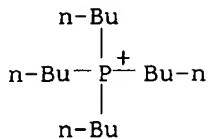
CM 5

CRN 65086-74-0
CMF C8 H5 O7 S



CM 6

CRN 15853-37-9
CMF C16 H36 P



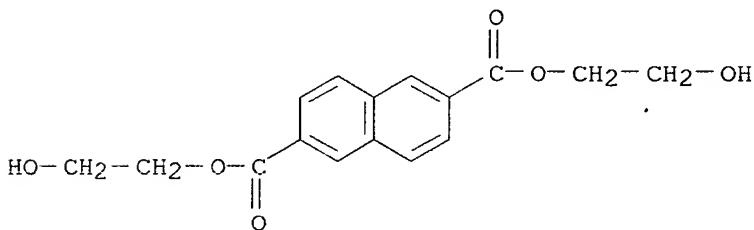
RN 247027-07-2 CAPLUS

CN Phosphonium, tetrabutyl-, salt with 5-sulfo-1,3-benzenedicarboxylic acid (1:1), polymer with bis(2-hydroxyethyl) 2,6-naphthalenedicarboxylate, 1,2-ethanediol, 2,6-naphthalenedicarboxylic acid and 2,2'-oxybis[ethanol] (9CI) (CA INDEX NAME)

CM 1

CRN 22374-96-5

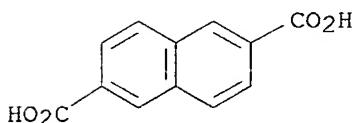
CMF C16 H16 O6



CM 2

CRN 1141-38-4

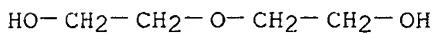
CMF C12 H8 O4



CM 3

CRN 111-46-6

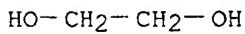
CMF C4 H10 O3



CM 4

CRN 107-21-1

CMF C2 H6 O2

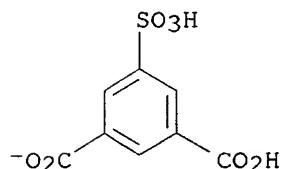


CM 5

CRN 65120-26-5
CMF C16 H36 P . C8 H5 O7 S

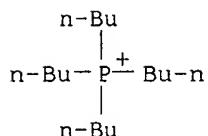
CM 6

CRN 65086-74-0
CMF C8 H5 O7 S



CM 7

CRN 15853-37-9
CMF C16 H36 P

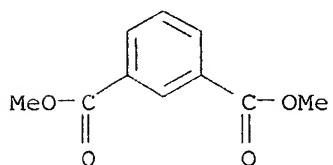


RN 247027-08-3 CAPLUS

CN Phosphonium, tetrabutyl-, salt with 5-sulfo-1,3-benzenedicarboxylic acid (1:1), polymer with dimethyl 1,3-benzenedicarboxylate, dimethyl 2,6-naphthalenedicarboxylate, 1,2-ethanediol and 2,2'-oxybis[ethanol] (9CI) (CA INDEX NAME)

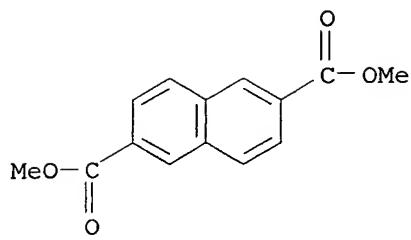
CM 1

CRN 1459-93-4
CMF C10 H10 O4



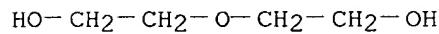
CM 2

CRN 840-65-3
CMF C14 H12 O4



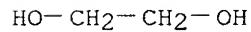
CM 3

CRN 111-46-6
CMF C4 H10 O3



CM 4

CRN 107-21-1
CMF C2 H6 O2

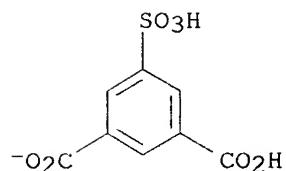


CM 5

CRN 65120-26-5
CMF C16 H36 P . C8 H5 O7 S

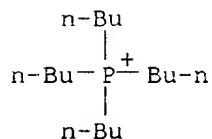
CM 6

CRN 65086-74-0
CMF C8 H5 O7 S



CM 7

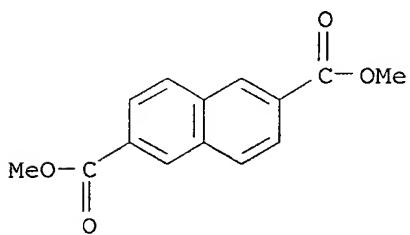
CRN 15853-37-9
CMF C16 H36 P



RN 256957-76-3 CAPLUS
CN Phosphonium, tetrabutyl-, salt with 5-sulfo-1,3-benzenedicarboxylic acid
(1:1), polymer with dimethyl 1,4-benzenedicarboxylate, dimethyl
2,6-naphthalenedicarboxylate, 1,2-ethanediol and 2,2'-oxybis[ethanol]
(9CI) (CA INDEX NAME)

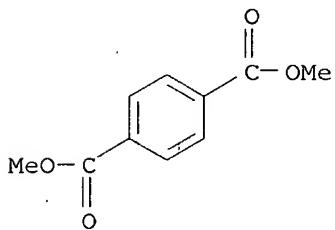
CM 1

CRN 840-65-3
CMF C14 H12 O4



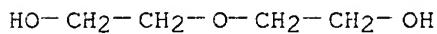
CM 2

CRN 120-61-6
CMF C10 H10 O4



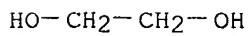
CM 3

CRN 111-46-6
CMF C4 H10 O3



CM 4

CRN 107-21-1
CMF C2 H6 O2

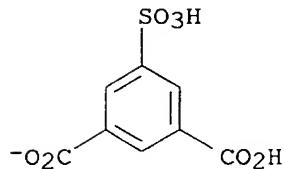


CM 5

CRN 65120-26-5
CMF C16 H36 P . C8 H5 O7 S

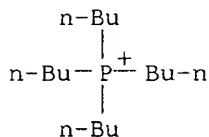
CM 6

CRN 65086-74-0
CMF C8 H5 O7 S



CM 7

CRN 15853-37-9
CMF C16 H36 P



L19 ANSWER 4 OF 7 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1999:64736 CAPLUS
DOCUMENT NUMBER: 130:117371
TITLE: Coating composition for ink receptor layer improved in the fixation of ink and water resistance, and process for the preparation thereof
INVENTOR(S): Takagi, Jinichi; Nakatani, Masaru; Nishita, Hayato; Murata, Sakae
PATENT ASSIGNEE(S): Takamatsu Oil & Fat Co., Ltd., Japan
SOURCE: PCT Int. Appl., 28 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9902350	A1	19990121	WO 1997-JP2980	19970827 <--
W: KR, US				
RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
JP 11029738	A2	19990202	JP 1997-185640	19970711 <--
EP 995609	A1	20000426	EP 1997-937806	19970827 <--
EP 995609	B1	20030416		
R: CH, DE, FR, LI				
US 6541567	B1	20030401	US 1999-446500	19991221
PRIORITY APPLN. INFO.:			JP 1997-185640	A 19970711
			WO 1997-JP2980	W 19970827

AB The invention relates to a coating composition for ink receptor layers which is excellent in the fixation of ink in ink jet printing, water resistance,

transparency, and the clarity of recorded images. The composition comprises an anionic graft polymer (1) prepared by grafting a resin mixture (A) comprising 100 to 10 % by weight of the water-base polyester resin having an average mol. weight of 4000 to 30000 and 0 to 90 % by weight of a water-base urethane resin with a monomer mixture (C) comprising 100 to 60 % by weight of a hydrophilic radical-polymerizable vinyl monomer and 0 to 40 % by weight of other copolymerizable vinyl monomer in an aqueous solution or dispersion (B) of a polyvinyl alc. having a degree of saponification of 75 to 100 % and a d.p. of

500

to 5000, and a modified cationic polymer (2) prepared by mixing a copolymer (D) comprising 10 to 100 % by weight of a radical-polymerizable vinyl monomer having a cationic quaternary ammonium group on the side chain and 90 to 0 % by weight of other copolymerizable vinyl monomer with a polyvinyl alc. (E) having a degree of saponification of 75 to 100 % and

a

d.p. of 500 to 5000.

IT

219662-84-7P 219662-85-8P

RL: DEV (Device component use); MSC (Miscellaneous); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)

(coating composition for ink-jet printing sheet ink receptor layer)

RN

219662-84-7 CAPLUS

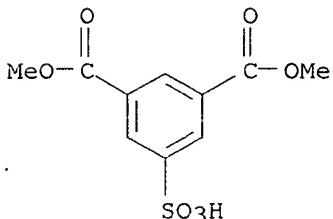
CN

1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with dimethyl 1,2-benzenedicarboxylate, dimethyl 1,3-benzenedicarboxylate, 2,2-dimethyl-1,3-propanediol, 1,2-ethanediol and 2-hydroxyethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

CM 1

CRN 3965-55-7

CMF C10 H10 O7 S . Na

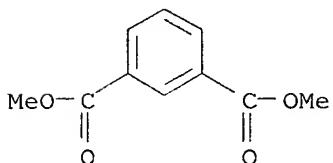


● Na

CM 2

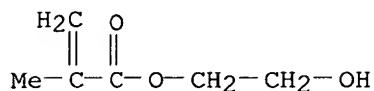
CRN 1459-93-4

CMF C10 H10 O4



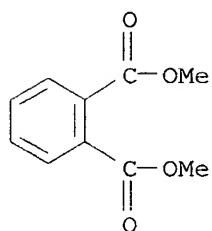
CM 3

CRN 868-77-9
CMF C6 H10 O3



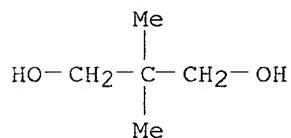
CM 4

CRN 131-11-3
CMF C10 H10 O4



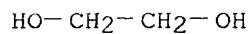
CM 5

CRN 126-30-7
CMF C5 H12 O2



CM 6

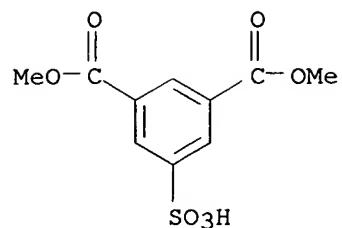
CRN 107-21-1
CMF C2 H6 O2



RN 219662-85-8 CAPLUS
CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, polymer with dimethyl 1,2-benzenedicarboxylate, dimethyl 1,3-benzenedicarboxylate, 2,2-dimethyl-1,3-propanediol and 1,2-ethanediol, graft (9CI) (CA INDEX NAME)

CM 1

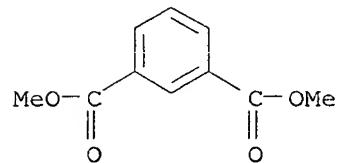
CRN 3965-55-7
CMF C10 H10 O7 S . Na



● Na

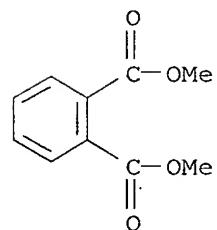
CM 2

CRN 1459-93-4
CMF C10 H10 O4



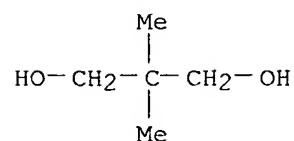
CM 3

CRN 131-11-3
CMF C10 H10 O4



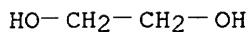
CM 4

CRN 126-30-7
CMF C5 H12 O2



CM 5

CRN 107-21-1
CMF C2 H6 O2



IT 219662-82-5P

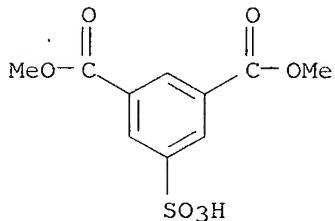
RL: DEV (Device component use); SPN (Synthetic preparation); PREP (Preparation); USES (Uses)
(coating composition for ink-jet printing sheet ink receptor layer)

RN 219662-82-5 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with dimethyl 1,2-benzenedicarboxylate, dimethyl 1,3-benzenedicarboxylate, 2,2-dimethyl-1,3-propanediol and 1,2-ethanediol (9CI) (CA INDEX NAME)

CM 1

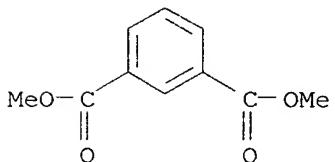
CRN 3965-55-7
CMF C10 H10 O7 S . Na



• Na

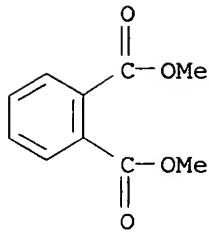
CM 2

CRN 1459-93-4
CMF C10 H10 O4



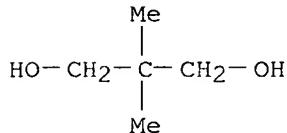
CM 3

CRN 131-11-3
CMF C10 H10 O4



CM 4

CRN 126-30-7
CMF C5 H12 O2



CM 5

CRN 107-21-1
CMF C2 H6 O2

HO—CH₂—CH₂—OH

REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L19 ANSWER 5 OF 7 CAPLUS COPYRIGHT 2006 ACS on STN
 ACCESSION NUMBER: 1997:802169 CAPLUS
 DOCUMENT NUMBER: 128:89633
 TITLE: Antibacterial polymer composition with excellent durability and safety
 INVENTOR(S): Arimori, So; Yokota, Hideyuki; Seko, Masahiro; Tanaka, Masakazu
 PATENT ASSIGNEE(S): Toyobo Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	-----	-----	-----	-----
JP 09324070	A2	19971216	JP 1996-142898	19960605 <--
PRIORITY APPLN. INFO.:			JP 1996-142898	19960605

OTHER SOURCE(S): MARPAT 128:89633

AB Title composition is obtained by adding organic acid-quaternary ammonium salt compound to synthetic polymer. Thus, 71.6 parts Na di-n-octyl 5-sulfoisophthalate was reacted with 50.0 parts benzalkonium chloride to give 100 parts complex. Then, poly(vinyl chloride) 100, di-2-ethylhexyl phthalate 60, epoxidized soybean oil 5, the complex 2, Zn

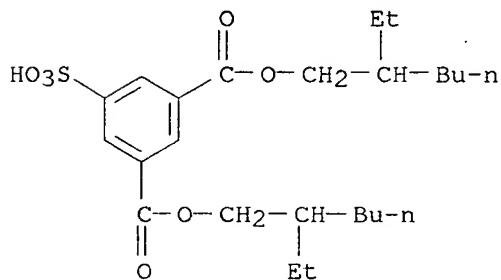
stearate 0.2, and Ca stearate 0.3 part were blended and molded to give film showing good antibacterial property and excellent dissoln. resistance.

IT 51307-83-6DP, benzalkonium salts 193752-86-2DP,
benzalkonium salts 193752-88-4DP, benzalkonium salts
193752-91-9DP, benzalkonium salts

RL: BAC (Biological activity or effector, except adverse); BSU (Biological study, unclassified); IMF (Industrial manufacture); MOA (Modifier or additive use); BIOL (Biological study); PREP (Preparation); USES (Uses) (antibacterial polymer compns. containing organic acid quaternary ammonium salts)

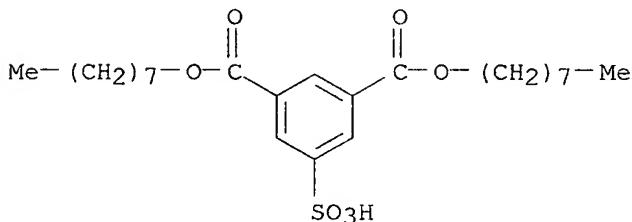
RN 51307-83-6 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-bis(2-ethylhexyl) ester (9CI) (CA INDEX NAME)



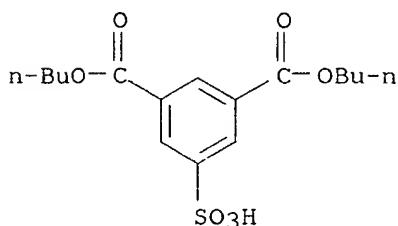
RN 193752-86-2 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dioctyl ester (9CI) (CA INDEX NAME)



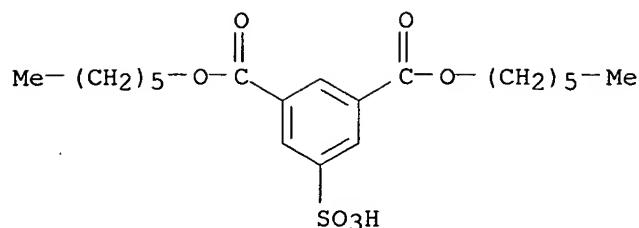
RN 193752-88-4 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dibutyl ester (9CI) (CA INDEX NAME)



RN 193752-91-9 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dihexyl ester (9CI) (CA INDEX NAME)



L19 ANSWER 6 OF 7 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1994:10545 CAPLUS

DOCUMENT NUMBER: 120:10545

TITLE: Concentrated dampening water composition for lithographic printing

INVENTOR(S): Matsumoto, Hiroshi; Kunichika, Kenji

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: U.S., 14 pp.

CODEN: USXXAM

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	-----	-----	-----	-----
US 5221330	A	19930622	US 1992-889391	19920528 <--
PRIORITY APPLN. INFO.:			JP 1991-126127	A 19910529
			JP 1991-138039	A 19910610
			JP 1991-275318	A 19911023
			JP 1991-283253	A 19911029

OTHER SOURCE(S): MARPAT 120:10545

AB The compns. comprise 0.1-10% hydrophilic polymer, 0.01-15% pH buffering agents, 5-80% water-miscible polyoxyalkylene monoalkyl ethers or polyethers as solvents, 0.05-10% aromatic sulfonates and/or onium compds. of B, P or N, and 30-80% H₂O. Thus, an aqueous composition containing hydroxypropyl

cellulose 6, buffering agents 19, ethoxylated octylene glycol 20, diethylene glycol mono-Bu ether 250, Na benzenesulfonate (I) 20, Ph₄PBr 5, nitric acid salts 15, and water to 1000 parts showed good smudge prevention, vs. poor without I and Ph₄PBr.

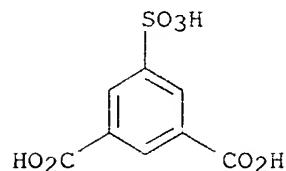
IT 6362-79-4

RL: USES (Uses)

(dampening water compns. containing, in lithog. printing)

RN 6362-79-4 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, monosodium salt (9CI) (CA INDEX NAME)



● Na

L19 ANSWER 7 OF 7 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1985:407697 CAPLUS

DOCUMENT NUMBER: 103:7697

TITLE: Polyester composition

INVENTOR(S): Kunugi, Katsuo; Suzuki, Togi; Konishi, Tadashi;
Ohwaki, Shinji

PATENT ASSIGNEE(S): Teijin Ltd. , Japan

SOURCE: U.S., 18 pp.

CODEN: USXXAM

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 4513114	A	19850423	US 1984-636912	19840802 <--
EP 169926	A1	19860205	EP 1984-109148	19840802 <--
EP 169926 R: DE, FR, GB	B1	19880518		
JP 61111358	A2	19860529	JP 1985-169715	19850802 <--
JP 03044584	B4	19910708		

PRIORITY APPLN. INFO.: US 1984-636912 19840802

AB Polyester compns. for fibers which exhibit excellent high-speed melt-spinning properties comprise 100 parts of a matrix polyester having intrinsic viscosity ≥ 0.300 and containing >80 mol% polyethylene terephthalate(I) repeating units and 0.2-7 parts dispersed phase in the form of primary fine particles and/or secondary agglomerates containing ≥ 1 phosphate compound, ≥ 1 alkaline earth metal compound, and ≥ 1 quaternary ammonium or phosphonium dispersing agent. The dispersed phase must satisfy the melt viscosity increase parameter in a polyester matrix having intrinsic viscosity 0.640. Thus, Ca(OAc)₂ [62-54-4] 0.57, Et₄NOH [77-98-5] 0.0075, Ca(OAc)₂-(MeO)₃PO reaction product 9.31, Sb₂O₃ 0.06, di-Me terephthalate 100, and ethylene glycol 60 parts were mixed, heated at 240° under atmospheric pressure with temperature increasing to 280° over 1.5 h and pressure

dropping to 1 mm Hg over 1 h, and heated 3 h at 280° under 1 mm Hg pressure to give I, which was melt spun at 6000 m/min to give filaments having tensile strength 3.9 g/denier, ultimate elongation 92%, birefringence 78 + 103, d. 1.353 g/cm³, and no recurrence of breakage (<0 times/100 kg).

IT 65483-33-2

RL: USES (Uses)
(containing dispersed alkaline earth compds. and phosphates, for melt-spun fibers)

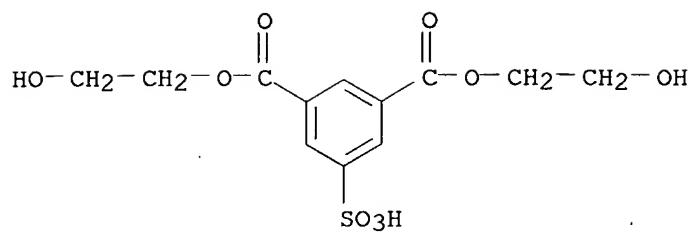
RN 65483-33-2 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-bis(2-hydroxyethyl) ester, monosodium salt, polymer with dimethyl 1,4-benzenedicarboxylate and 1,2-ethanediol (9CI) (CA INDEX NAME)

CM 1

CRN 24019-46-3

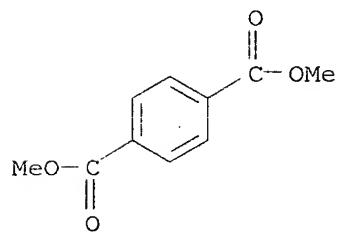
CMF C12 H14 O9 S . Na



● Na

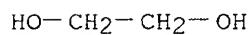
CM 2

CRN 120-61-6
CMF C10 H10 O4



CM 3

CRN 107-21-1
CMF C2 H6 O2



=>

=> d 1-6 ibib abs hitstr

L15 ANSWER 1 OF 6 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1999:31998 CAPLUS
DOCUMENT NUMBER: 130:82358
TITLE: Antibacterial polymeric moldings
INVENTOR(S): Monden, Noriko; Seko, Masahiro; Yokota, Hideyuki;
Tanaka, Masakazu; Arimori, Susumu
PATENT ASSIGNEE(S): Toyo Boseki Kabushiki Kaisha, Japan
SOURCE: Eur. Pat. Appl., 14 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

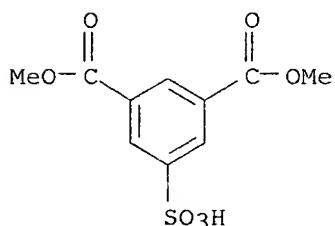
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 887373	A2	19981230	EP 1998-111536	19980623 <--
EP 887373	A3	20010912		
R: AT, BE, CH, IE, SI, LT,	DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, LV, FI, RO			
JP 11009681	A2	19990119	JP 1997-165978	19970623 <--
JP 11047260	A2	19990223	JP 1997-211790	19970806 <--
JP 11206873	A2	19990803	JP 1998-16765	19980129 <--
JP 11216177	A2	19990810	JP 1998-21051	19980202 <--
JP 11290449	A2	19991026	JP 1998-96002	19980408 <--
JP 11309158	A2	19991109	JP 1998-116831	19980427 <--
PRIORITY APPLN. INFO.:			JP 1997-165978	A 19970623
			JP 1997-211790	A 19970806
			JP 1998-16765	A 19980129
			JP 1998-21051	A 19980202
			JP 1998-96002	A 19980408
			JP 1998-116831	A 19980427

AB The moldings contain anionic compds. capable of combining, by ionic bonds, with cationic components of water-soluble antibacterial agents, wherein the cationic components are combined with the anionic compds. by ionic bonds at least at the surface of the moldings. Thus, a latex for dipping of an urethral catheter was prepared from a natural rubber containing zinc dimethyldithiocarbamate, S colloid, activated Zn, and Na dimethyl-5-sulfoisophthalate.

IT 3965-55-7, Sodium dimethyl-5-sulfoisophthalate
RL: BUU (Biological use, unclassified); MOA (Modifier or additive use); BIOL (Biological study); USES (Uses)
(antibacterial polymeric moldings)

RN 3965-55-7 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt (9CI) (CA INDEX NAME)



● Na

L15 ANSWER 2 OF 6 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1997:699281 CAPLUS

DOCUMENT NUMBER: 127:359830

TITLE: Electrically conductive polyurethanes and moldings containing them

INVENTOR(S): Tsunoda, Shohei; Konishi, Shin

PATENT ASSIGNEE(S): Nippon Polyurethane Industry Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

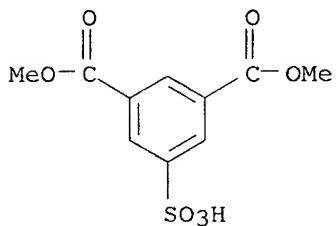
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09278863	A2	19971028	JP 1996-111936	19960409 <--
PRIORITY APPLN. INFO.:			JP 1996-111936	19960409
AB	Title polyurethanes have Tg of $\leq 30^\circ$ and volume intrinsic resistivity 106-109 $\Omega\text{-cm}$, and contains 1 ionic segment bearing sulfonic acid groups or their salts, carboxylic acid groups or their salts, tertiary amine groups, or quaternary ammonium groups. Thus, polymerizing a polyester polyol derived from adipic acid and 1,4-butanediol with a polyester polyol derived from adipic acid, di-Me 5-sodiosulfoisophthalate and 1,4-butanediol, and MDI in MEK/PhMe gave a polyurethane, 100 parts of which was combined with 10 parts Coronate L, coated on a release paper, dried, and cured at 120° for 2 h to give a transparent cast film with volume intrinsic resistivity 108.5 $\Omega\text{-cm}$ and Tg -33°.			
IT	198484-65-0P, Adipic acid-1,4-butanediol-Coronate L-dimethyl 5-sodiosulfoisophthalate-MDI block copolymer 198484-66-1P, Adipic acid-1,4-butanediol-Coronate HX-dimethyl 5-sodiosulfoisophthalate-1,6-hexanediol-TDI block copolymer 198484-68-3P, Adipic acid-1,4-butanediol-Coronate L-dimethylolpropionic acid-dimethyl 5-sodiosulfoisophthalate-MDI-polyethylene glycol block copolymer 198484-69-4P, Adipic acid-1,4-butanediol-Coronate HX-dimethylolpropionic acid-dimethyl 5-sodiosulfoisophthalate-isophorone diamine-MDI-monoethanolamine-polyethylene glycol block copolymer 198484-72-9P, Adipic acid-1,4-butanediol-Coronate HX-2,2-dimethylolbutanoic acid-dimethyl 5-sodiosulfoisophthalate-ethylene oxide-MDI-propylene oxide block copolymer 198484-74-1P, Adipic acid-Coronate HX-dimethyl 5-sodiosulfoisophthalate-2-ethyl-2-butyl-1,3-propanediol-MDI copolymer 198484-75-2P, Adipic acid-1,4-butanediol-dimethyl 5-sodiosulfoisophthalate-MDI-trimethylolpropane block copolymer 198484-76-3P, Adipic acid-1,4-butanediol-dimethylolpropionic acid-dimethyl 5-sodiosulfoisophthalate-ethylene oxide-MDI-propylene oxide-trimethylolpropane block copolymer 198484-78-5P, Adipic acid-1,4-butanediol-Coronate HX-dimethyl 5-sodiosulfoisophthalate-polyethylene glycol block copolymer			
	RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (rubber; manufacture of highly elec. conductive polyurethanes for molding materials)			
RN	198484-65-0 CAPLUS			
CN	1,3-Benzene dicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with 1,4-butanediol, Coronate L, hexanedioic acid and 1,1'-methylenebis[4-isocyanatobenzene], block (9CI) (CA INDEX NAME)			

CRN 39278-79-0
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

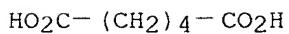
CRN 3965-55-7
CMF C10 H10 O7 S . Na



● Na

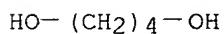
CM 3

CRN 124-04-9
CMF C6 H10 O4



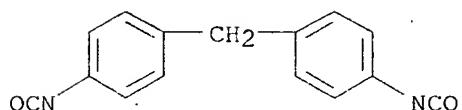
CM 4

CRN 110-63-4
CMF C4 H10 O2



CM 5

CRN 101-68-8
CMF C15 H10 N2 O2



RN 198484-66-1 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with 1,4-butanediol, Coronate HX, 1,3-diisocyanatomethylbenzene,

hexanedioic acid and 1,6-hexanediol, block (9CI) (CA INDEX NAME)

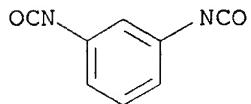
CM 1

CRN 144245-98-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

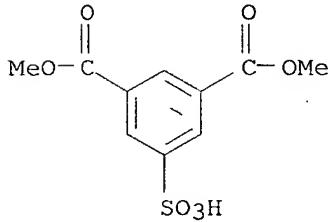
CRN 26471-62-5
CMF C9 H6 N2 O2
CCI IDS



D1--Me

CM 3

CRN 3965-55-7
CMF C10 H10 O7 S . Na



● Na

CM 4

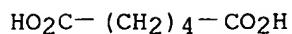
CRN 629-11-8
CMF C6 H14 O2

HO-(CH₂)₆-OH

CM 5

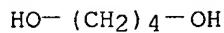
CRN 124-04-9

CMF C6 H10 O4



CM 6

CRN 110-63-4
CMF C4 H10 O2



RN 198484-68-3 CAPLUS
CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt,
polymer with 1,4-butanediol, Coronate L, hexanedioic acid,
 α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl),
3-hydroxy-2-(hydroxymethyl)-2-methylpropanoic acid and
1,1'-methylenebis[4-isocyanatobenzene], block (9CI) (CA INDEX NAME)

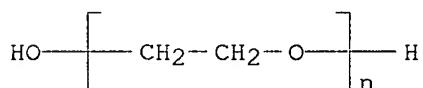
CM 1

CRN 39278-79-0
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

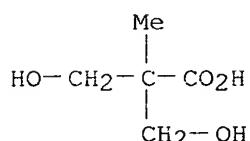
CM 2

CRN 25322-68-3
CMF (C2 H4 O)n H2 O
CCI PMS



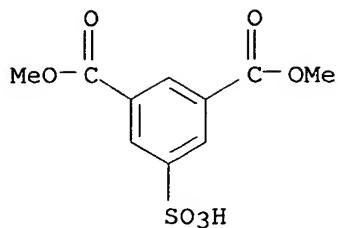
CM 3

CRN 4767-03-7
CMF C5 H10 O4



CM 4

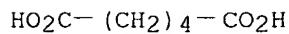
CRN 3965-55-7
CMF C10 H10 O7 S . Na



● Na

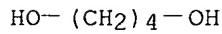
CM 5

CRN 124-04-9
CMF C6 H10 O4



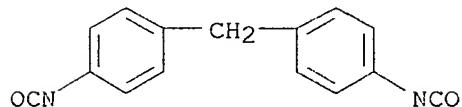
CM 6

CRN 110-63-4
CMF C4 H10 O2



CM 7

CRN 101-68-8
CMF C15 H10 N2 O2



RN 198484-69-4 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with 2-aminoethanol, 5-amino-1,3,3-trimethylcyclohexanemethanamine, 1,4-butanediol, Coronate HX, hexanedioic acid, α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl), 3-hydroxy-2-(hydroxymethyl)-2-methylpropanoic acid and 1,1'-methylenebis[4-isocyanatobenzene], block (9CI) (CA INDEX NAME)

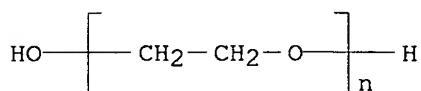
CM 1

CRN 144245-98-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

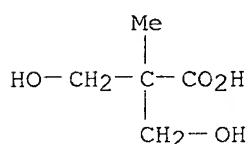
CM 2

CRN 25322-68-3
CMF (C₂ H₄ O)_n H₂ O
CCI PMS



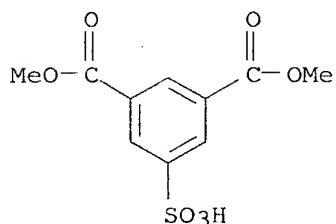
CM 3

CRN 4767-03-7
CMF C₅ H₁₀ O₄



CM 4

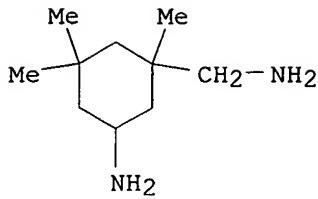
CRN 3965-55-7
CMF C₁₀ H₁₀ O₇ S . Na



● Na

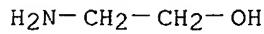
CM 5

CRN 2855-13-2
CMF C₁₀ H₂₂ N₂



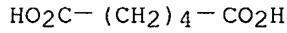
CM 6

CRN 141-43-5
CMF C2 H7 N O



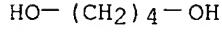
CM 7

CRN 124-04-9
CMF C6 H10 O4



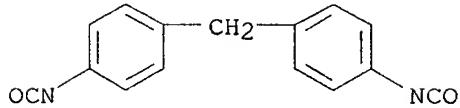
CM 8

CRN 110-63-4
CMF C4 H10 O2



CM 9

CRN 101-68-8
CMF C15 H10 N2 O2



RN 198484-72-9 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with 2,2-bis(hydroxymethyl)butanoic acid, 1,4-butanediol, Coronate HX, hexanedioic acid, 1,1'-methylenebis[4-isocyanatobenzene], methyloxirane and oxirane, block (9CI) (CA INDEX NAME)

CM 1

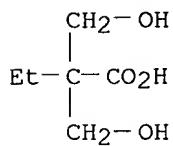
CRN 144245-98-7
CMF Unspecified

CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

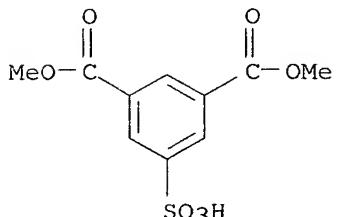
CM 2

CRN 10097-02-6
CMF C6 H12 O4



CM 3

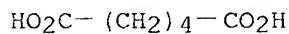
CRN 3965-55-7
CMF C10 H10 O7 S . Na



● Na

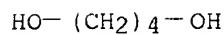
CM 4

CRN 124-04-9
CMF C6 H10 O4



CM 5

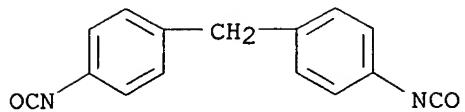
CRN 110-63-4
CMF C4 H10 O2



CM 6

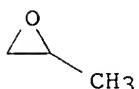
CRN 101-68-8

CMF C15 H10 N2 O2



CM 7

CRN 75-56-9
CMF C3 H6 O



CM 8

CRN 75-21-8
CMF C2 H4 O



RN 198484-74-1 CAPLUS
CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt,
polymer with 2-butyl-2-ethyl-1,3-propanediol, Coronate HX, hexanedioic
acid and 1,1'-methylenebis[4-isocyanatobenzene] (9CI) (CA INDEX NAME)

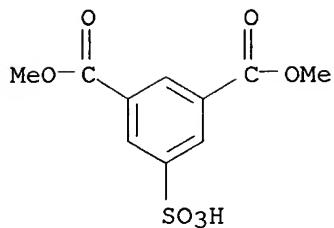
CM 1

CRN 144245-98-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

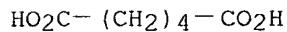
CRN 3965-55-7
CMF C10 H10 O7 S . Na



● Na

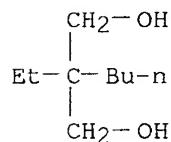
CM 3

CRN 124-04-9
CMF C6 H10 O4



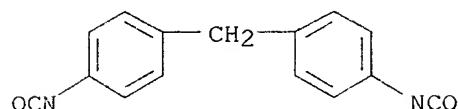
CM 4

CRN 115-84-4
CMF C9 H20 O2



CM 5.

CRN 101-68-8
CMF C15 H10 N2 O2

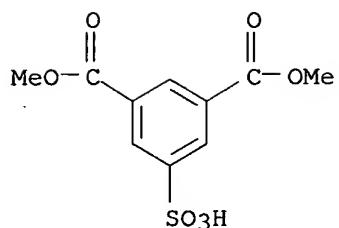


RN 198484-75-2 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with 1,4-butanediol, 2-ethyl-2-(hydroxymethyl)-1,3-propanediol, hexanedioic acid and 1,1'-methylenebis[4-isocyanatobenzene], block (9CI) (CA INDEX NAME)

CM 1

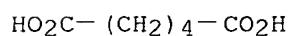
CRN 3965-55-7
CMF C10 H10 O7 S . Na



● Na

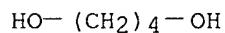
CM 2

CRN 124-04-9
CMF C6 H10 O4



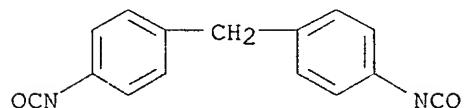
CM 3

CRN 110-63-4
CMF C4 H10 O2



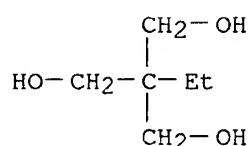
CM 4

CRN 101-68-8
CMF C15 H10 N2 O2



CM 5

CRN 77-99-6
CMF C6 H14 O3



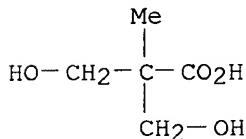
RN 198484-76-3 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with 1,4-butanediol, 2-ethyl-2-(hydroxymethyl)-1,3-propanediol, hexanedioic acid, 3-hydroxy-2-(hydroxymethyl)-2-methylpropanoic acid, 1,1'-methylenebis[4-isocyanatobenzene], methyloxirane and oxirane, block (9CI) (CA INDEX NAME)

CM 1

CRN 4767-03-7

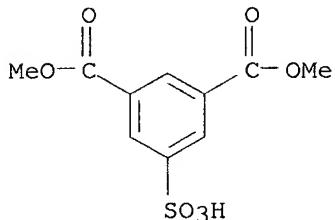
CMF C5 H10 O4



CM 2

CRN 3965-55-7

CMF C10 H10 O7 S . Na

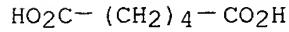


● Na

CM 3

CRN 124-04-9

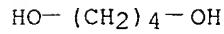
CMF C6 H10 O4



CM 4

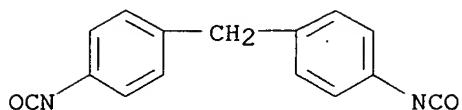
CRN 110-63-4

CMF C4 H10 O2



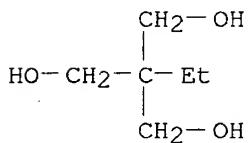
CM 5

CRN 101-68-8
CMF C15 H10 N2 O2



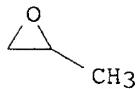
CM 6

CRN 77-99-6
CMF C6 H14 O3



CM 7

CRN 75-56-9
CMF C3 H6 O



CM 8

CRN 75-21-8
CMF C2 H4 O



RN 198484-78-5 CAPLUS
CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with 1,4-butanediol, Coronate HX, hexanedioic acid and α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl), block (9CI) (CA INDEX NAME)

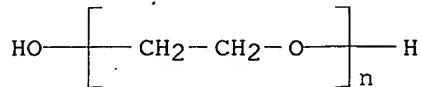
CM 1

CRN 144245-98-7
CMF Unspecified
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

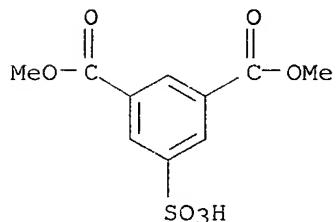
CM 2

CRN 25322-68-3
CMF (C₂H₄O)_nH₂O
CCI PMS



CM 3

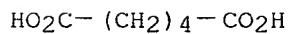
CRN 3965-55-7
CMF C₁₀H₁₀O₇S.Na



● Na

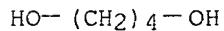
CM 4

CRN 124-04-9
CMF C₆H₁₀O₄



CM 5

CRN 110-63-4
CMF C₄H₁₀O₂



L15 ANSWER 3 OF 6 CAPLUS COPYRIGHT 2006 ACS on STM
ACCESSION NUMBER: 1997:310129 CAPLUS
DOCUMENT NUMBER: 126:279058
TITLE: Active energy ray-curable acrylic compositions for
antistatic hard coatings and synthetic resin moldings
thereof
INVENTOR(S): Katsukawa, Makoto; Hibino, Kenichi; Yoshida, Michiro

PATENT ASSIGNEE(S): Sanyo Chemical Ind Ltd, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09053025	A2	19970225	JP 1995-227549	19950811 <--
JP 2964220	B2	19991018		

PRIORITY APPLN. INFO.: JP 1995-227549 19950811
 AB The compns. comprise (A) compds. with ≥ 1 (meth)acryloyl group and ≥ 3 ionic groups which are separated with nonionic chains whose total number of C, O, and N is 2-30, (B) monomers with ≥ 2 (meth)acryloyl groups, and optionally (C) oligomers with ≥ 2 (meth)acryloyl groups and show mol. weight 800-4000. Moldings covered with the cured coatings are also claimed. Thus, transesterifying 357 parts N-methyldiethanolamine (I) and 348 parts di-Me adipate (II) at 120° in the presence of dibutyltin oxide to give a OH-terminated prepolymer (I:II = 3:2), adding 200 parts H₂O, adding dropwise 378 parts Me₂SO₄ for quaternization, and aging at 70° gave a quaternized compound with OH terminals, 955 parts of which was transesterified with 72 parts Me acrylate while removing MeOH to give an acryloyl-terminated compound A mixture of Light Ester PE 3A (pentaerythritol triacrylate) 92, the obtained compound 5, and Darocur 1173 3 parts was applied onto a poly(Me methacrylate) plate and exposed to UV to give a cured coating showing surface sp. resistivity 8 + 1012 Ω and pencil hardness 5H.

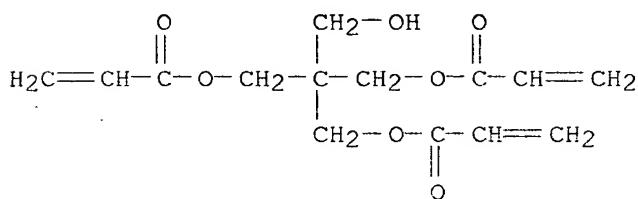
IT 188899-30-1P 188958-53-4P
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (UV-curable quaternized acrylic compns. for antistatic hard coatings on resin moldings)

RN 188899-30-1 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt, polymer with α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl), 2-propenoate, polymer with 2-(hydroxymethyl)-2-[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 3524-68-3
CMF C14 H18 O7

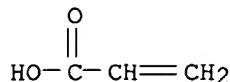


CM 2

CRN 188899-29-8
CMF (C₁₀ H₁₀ O₇)_n H₂O . Na)x . x C₃ H₄ O₂

CM 3

CRN 79-10-7
CMF C3 H4 O2

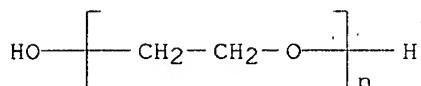


CM 4

CRN 110064-38-5
CMF (C₁₀ H₁₀ O₇ S . (C₂ H₄ O)_n H₂ O . Na)x
CCI PMS

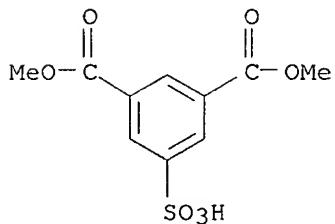
CM 5

CRN 25322-68-3
CMF (C₂ H₄ O)_n H₂ O
CCI PMS



CM 6

CRN 3965-55-7
CMF C₁₀ H₁₀ O₇ S . Na

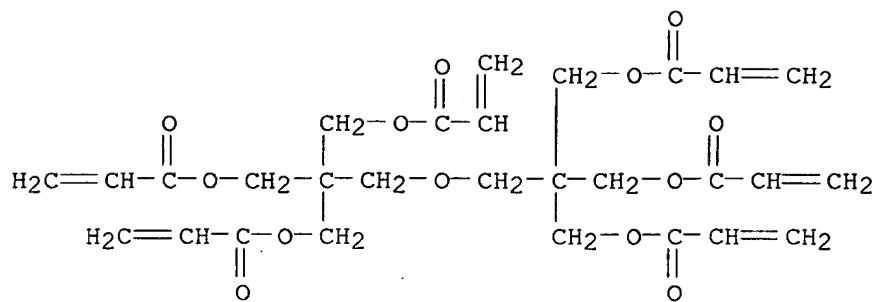


● Na

RN 188958-53-4 CAPLUS
CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, 1,3-dimethyl ester, sodium salt,
polymer with α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl),
2-propenoate, polymer with 2-(hydroxymethyl)-2-[(1-oxo-2-
propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate and
2-[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[[1-oxo-2-
propenyl)oxy]methyl]propoxy]methyl]-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-
propanediyl di-2-propenoate (9CI) (CA INDEX NAME)

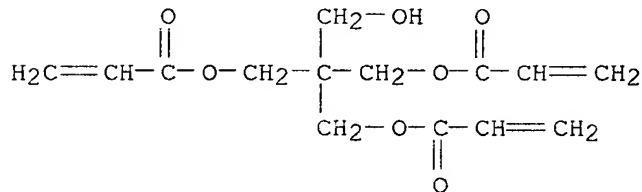
CM 1

CRN 29570-58-9
CMF C28 H34 O13



CM 2

CRN 3524-68-3
CMF C14 H18 O7

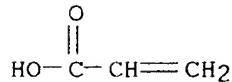


CM 3

CRN 188899-29-8
CMF (C10 H10 O7 S . (C2 H4 O)n H2 O . Na)x . x C3 H4 O2

CM 4

CRN 79-10-7
CMF C3 H4 O2

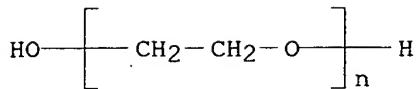


CM 5

CRN 110064-38-5
CMF (C10 H10 O7 S . (C2 H4 O)n H2 O . Na)x
CCI PMS

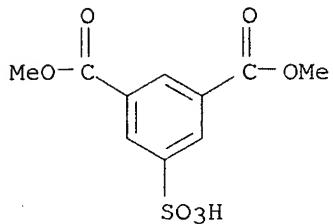
CM 6

CRN 25322-68-3
CMF (C2 H4 O)n H2 O
CCI PMS



CM 7

CRN 3965-55-7
CMF C10 H10 O7 S . Na



• Na

L15 ANSWER 4 OF 6 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1997:259659 CAPLUS

DOCUMENT NUMBER: 126:239191

TITLE: Thermoplastic resin compositions giving moldings superior in transparency and antistatic property

INVENTOR(S): Kido, Nobuaki; Matsumura, Shunichi; Ito, Takashi

PATENT ASSIGNEE(S): Teijin Ltd., Japan

SOURCE: Eur. Pat. Appl., 22 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 759459	A2	19970226	EP 1996-305831	19960808 <--
EP 759459	A3	19971001		
EP 759459	B1	20010103		
R: DE, FR, GB				
KR 230631	B1	19991115	KR 1996-33078	19960808 <--
AU 9661979	A1	19970220	AU 1996-61979	19960809 <--
AU 706442	B2	19990617		
JP 09249805	A2	19970922	JP 1996-213661	19960813 <--
JP 3251507	B2	20020128		
JP 09176412	A2	19970708	JP 1996-214558	19960814 <--
JP 3634510	B2	20050330		
CA 2183412	AA	19970218	CA 1996-2183412	19960815 <--
CA 2183412	C	20030909		
CN 1149601	A	19970514	CN 1996-113343	19960817 <--
CN 1095860	B	20021211		
PRIORITY APPLN. INFO.:			JP 1995-209506	A 19950817
			JP 1995-274079	A 19951023

JP 1995-305721	A 19951124
JP 1995-317945	A 19951206
JP 1995-318966	A 19951207
JP 1995-318967	A 19951207
JP 1996-1292	A 19960109

AB A thermoplastic resin composition comprises 100 parts by weight of a thermoplastic

resin (A) having a refractive index of 1.52 to 1.61 and a haze of 40 or less, and 5 to 40 parts by weight of a polyether ester (B) which has a sulfonate group and a polyalkylene oxide group, and is substantially immiscible with the thermoplastic resin (A), the difference in the refractive index between the thermoplastic resin (A) and the polyether ester (B) being 0.04 or less. This composition further contains an ionic surfactant. Moldings from this composition have a haze of 40% or less, a surface resistivity of 1 + 1010 to 1 + 1014 ohm/square, and low water-wash-out of the surfactant. A typical composition contained 100 parts bisphenol A polycarbonate and 13.7 parts mixture of 500 parts Na isopropylnaphthalenesulfonate and a polyester prepared by polymerization

of di-Me 2,6-naphthalenedicarboxylate 1074, di-Me 4-sodiosulfo-2,6-naphthalenedicarboxylate 381, 1,6-hexamethylene glycol 910, and polyethylene glycol 750 parts.

IT 188562-46-1P 188562-48-3P 188562-50-7P

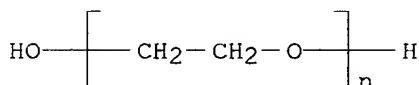
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); PREP (Preparation); USES (Uses)
(thermoplastic polymer blends with polyoxyalkylene-polyesters having sulfonate groups and anionic surfactants for transparent antistatic moldings)

RN 188562-46-1 CAPLUS

CN 2,6-Naphthalenedicarboxylic acid, dimethyl ester, polymer with 1,3-dimethyl 5-sulfo-1,3-benzenedicarboxylate sodium salt, 1,2-ethanediol, 1,6-hexanediol and α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl), block (9CI) (CA INDEX NAME)

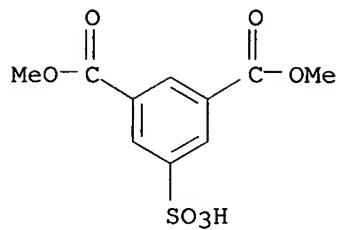
CM 1

CRN 25322-68-3
CMF (C₂ H₄ O)_n H₂ O
CCI PMS



CM 2

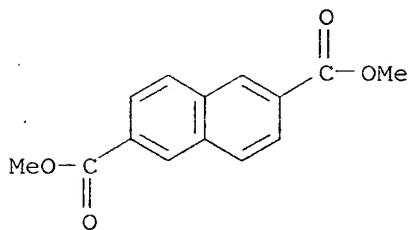
CRN 3965-55-7
CMF C₁₀ H₁₀ O₇ S . Na



● Na

CM 3

CRN 840-65-3
CMF C14 H12 O4



CM 4

CRN 629-11-8
CMF C6 H14 O2

HO—(CH₂)₆—OH

CM 5

CRN 107-21-1
CMF C₂ H₆ O₂

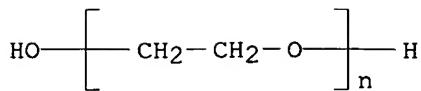
HO—CH₂—CH₂—OH

RN 188562-48-3 CAPLUS

CN [1,1'-Biphenyl]-4,4'-dicarboxylic acid, dimethyl ester, polymer with 1,3-dimethyl 5-sulfo-1,3-benzenedicarboxylate sodium salt, 1,2-ethanediol, 1,6-hexanediol and α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl), block (9CI) (CA INDEX NAME)

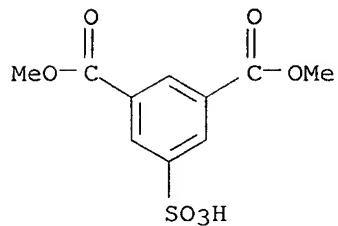
CM 1

CRN 25322-68-3
CMF (C₂ H₄ O)_n H₂ O
CCI PMS



CM 2

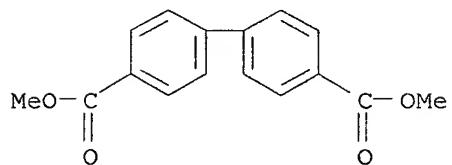
CRN 3965-55-7
CMF C₁₀ H₁₀ O₇ S . Na



• Na

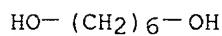
CM 3

CRN 792-74-5
CMF C₁₆ H₁₄ O₄



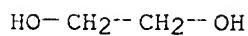
CM 4

CRN 629-11-8
CMF C₆ H₁₄ O₂



CM 5

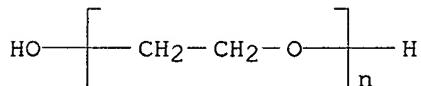
CRN 107-21-1
CMF C₂ H₆ O₂



RN 188562-50-7 CAPLUS
CN 2,6-Naphthalenedicarboxylic acid, dimethyl ester, polymer with
1,3-dimethyl 5-sulfo-1,3-benzenedicarboxylate sodium salt, 1,6-hexanediol
and α -hydro- ω -hydroxypoly(oxy-1,2-ethanediyl), block (9CI)
(CA INDEX NAME)

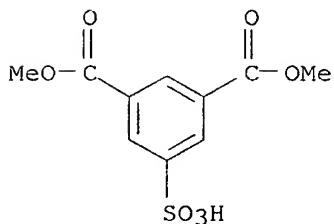
CM 1

CRN 25322-68-3
CMF (C₂ H₄ O)_n H₂ O
CCI PMS



CM 2

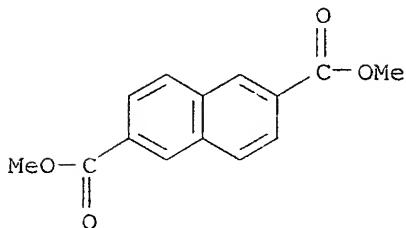
CRN 3965-55-7
CMF C₁₀ H₁₀ O₇ S . Na



● Na

CM 3

CRN 840-65-3
CMF C₁₄ H₁₂ O₄



CM 4

CRN 629-11-8
CMF C₆ H₁₄ O₂

HO-(CH₂)₆-OH

L15 ANSWER 5 OF 6 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1997:240385 CAPLUS
DOCUMENT NUMBER: 126:226404
TITLE: Antistatic agents and antimicrobial agents for silicones
INVENTOR(S): Kano, Toshihiko
PATENT ASSIGNEE(S): Sanyo Chemical Ind Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09031200	A2	19970204	JP 1995-290505	19951011 <--
JP 3115519	B2	20001211		
JP 2000290109	A2	20001017	JP 2000-72902	19951011 <--
PRIORITY APPLN. INFO.:			JP 1995-141329	A 19950515
			JP 1995-290505	A3 19951011

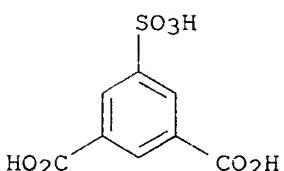
AB The title antistatic agents are organopolysiloxanes having ionic group-containing parts, and the title antimicrobial agents are organopolysiloxanes having ≥2 quaternary ammonium or phosphonium groups, e.g., Me₃SiO(SiMe₂O)_m[Si(Me){(CH₂)₃NHCH₂CH₂NH₂}₀]nSiMe₃ compound with di-Me carbonate or di-Me sulfate, for silicone rubbers such as KE-108.

IT 6362-79-4DP, 5-Sodiosulfoisophthalic acid, reaction products with trimethylsilyl-terminated dimethylsilanediol-(glycidyloxypropyl)methylsilane copolymer

RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(antistatic agent; antistatic agents and antimicrobial agents for silicones)

RN 6362-79-4 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, monosodium salt. (9CI) (CA INDEX NAME)



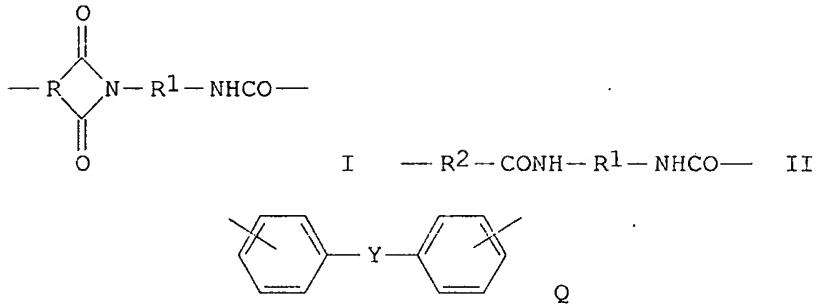
Na

L15 ANSWER 6 OF 6 CAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1994:247302 CAPLUS
DOCUMENT NUMBER: 120:247302
TITLE: Ionic group-containing polyamide-polyimides
INVENTOR(S): Oohashi, Hideyuki; Uno, Keiichi; Kurita, Tomoharu;

PATENT ASSIGNEE(S): Inukai, Tadashi
 SOURCE: Toyo Boseki, Japan
 Jpn. Kokai Tokkyo Koho, 10 pp.
 CODEN: JKXXAF

DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05255504	A2	19931005	JP 1992-55085	19920313 <--
JP 3168476	B2	20010521		
PRIORITY APPLN. INFO.: GI			JP 1992-55085	19920313



AB Title polymers, spinnable into fibers with good dyeability or useful for films and coatings, consist of structural units I and II [R = trivalent aromatic group; R1 = Q; Y = C1-5 alkylene, O, SO₂, CO, S, (substituted) biphenylene, (substituted) phenylene; R2 = divalent organic group; ≥1 of R, R1, and R2 contain 0.05-25 mol% carboxylates, phosphates, phosphonates, phosphinates, sulfonates, pyridinium salts, and/or quaternary ammonium salts]. The polymers may be bound to polyvalent metal ions up to equiv of their ionic groups. Thus, a mixture of trimellitic anhydride 0.09, Na 5-sulfoisophthalate 0.01, and MDI 0.10 mol was heated at 190° in N-methyl-2-pyrrolidone to give a sodiosulfo group-containing polyamide-polyimide with logarithmic viscosity 0.95, which was wet-spun, drawn 6-fold at 380°, and dyed with Diacryl Blue H2R-N to give blue fibers with high color yield.

IT 35429-01-7P

RL: IMF (Industrial manufacture); PREP (Preparation)
 (preparation of, for manufacture of fibers with good dyeability or heat-resistant films)

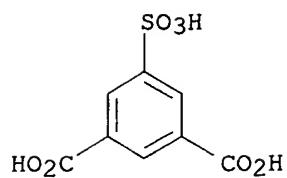
RN 35429-01-7 CAPLUS

CN 1,3-Benzenedicarboxylic acid, 5-sulfo-, monosodium salt, polymer with 1,3-dihydro-1,3-dioxo-5-isobenzofurancarboxylic acid and 1,1'-methylenebis[4-isocyanatobenzene] (9CI) (CA INDEX NAME)

CM 1

CRN 6362-79-4

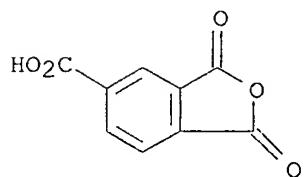
CMF C8 H6 O7 S . Na



● Na

CM 2

CRN 552-30-7
CMF C9 H4 O5



CM 3

CRN 101-68-8
CMF C15 H10 N2 O2

